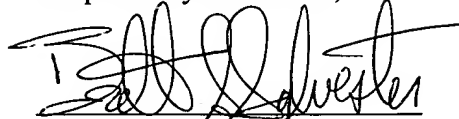


PRELIMINARY AMENDMENT
Continuation of U.S. Appln. No. 09/023,801

An action from the office is respectfully requested.

Respectfully submitted,



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APPENDIX

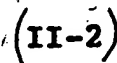
Marked up version of claims

6. (Amended) A positive [type] photoresist composition comprising a resin which



wherein R₂₁ to R₂₄, which may be the same or different, each represents a hydrogen atom or an alkyl group; and m represents 1 or 2.

7. (Amended) The positive [type] photoresist composition according to claim 6,



wherein R_{21} to R_{24} and m have the same meanings as given in claim 6; R_{25} represents a hydrogen atom or a methyl group; and A_{21} represents one group selected from the group consisting of a single bond, an alkylene group, a substituted alkylene group, an ether group, a thioether group, a carbonyl group, an ester group, an amido group, a sulfonamido group, a urethane group and a urea group, or a combination of two or more of them.

8. (Amended) The positive [type] photoresist composition according to claim 6 or 7, wherein said resin further contains repeating structure units each having an alicyclic hydrocarbon moiety.

9. (Amended) The positive [type] photoresist composition according to [any one of claims] claim 6 [to 8] or 7, wherein said resin further contains repeating structure units each having a group which is decomposed by action of an acid to increase solubility in an alkali developing solution.